Advanced Machine Learning, Pattern Recognition, and Deep Learning Technologies: Methodologies and Applications

Guest Editors:

Dr. Shuping Zhao

Dr. Jie Wen

Dr. Chao Huang

Dr. Bob Zhang

Deadline for manuscript submissions:
28 February 2025

Message from the Guest Editors

The aim of this topic is to highlight recent advances in machine learning, pattern recognition, and deep learning methodologies and theories. Papers with interesting/significant new applications of the above methods are also welcome. The topics of interest include, but are not limited to, the following:

1. Advanced machine intelligence methods and applications;
2. Advanced pattern analysis methods and applications;
3. Deep-learning-based methods and applications;
4. Biometric recognition algorithms and applications;
5. Multi-view/-modal learning and fusion;
6. Data mining and analysis;
7. Hashing learning-based methods and applications;
8. Dimensionality reduction and discriminant representation;
9. Subspace learning and clustering;
10. Graph learning-based methods and applications;
11. Image super-resolution/enhancing/restoration;
12. Advanced models in computer vision, such as object tracking and detection;
13. Sparse representation and application.

Special issue

Editor-in-Chief

Prof. Dr. Flavio Canavero
Department of Electronics and
Telecommunications,
Politecnico di Torino, 10129
Torino, Italy

Message from the Editor-in-Chief

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